IN THE CLAIMS:

Please amend Claims 5-10, 15-20, 24, 27, 28, 32, 35, and 36, as indicated below. The following is a complete listing of the claims, and replaces all previous versions and listings of claims in the present application.

Claim 1 (Original): A field effect transistor having an organic semiconductor layer, comprising:

an organic semiconductor layer containing at least porphyrin; and
a layer composed of at least a polysiloxane compound, the layer being
laminated on the organic semiconductor layer so as to be in intimate contact with the
organic semiconductor layer.

Claim 2 (Original): The field effect transistor according to claim 1, wherein the polysiloxane compound is represented by the following general formula (1): General formula (1)

$$\begin{array}{c|cccc}
R_1 & R_3 \\
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(In the formula, R_1 to R_4 each represent a substituted or unsubstituted alkyl or alkenyl group having 1 to 5 carbon atoms, a substituted or unsubstituted phenyl group, or a siloxane unit. R_1 to R_4 may be identical to or different from one another. n represents an integer of 1 or more.).

Claim 3 (Original): The field effect transistor according to claim 1, wherein the polysiloxane compound comprises a polysiloxane compound represented by the following general formula (2) and/or the following general formula (6):

General formula (2)

R₇

 R_{10} each represent a substituted or unsubstitute

(In the formula, R_7 to R_{10} each represent a substituted or unsubstituted alkyl or alkenyl group having 1 to 5 carbon atoms, or a substituted or unsubstituted phenyl group. R_7 to R_{10} may be identical to or different from one another. m and n each represent an integer of 0 or more, and a sum of m and n is an integer of 1 or more.) General formula (6):

$$\begin{array}{c|c}
 & R_{21} \\
 & Si \\
 & Si \\
 & R_{22}
\end{array}$$

$$\begin{array}{c|c}
 & R_{23} \\
 & Si \\
 & Si \\
 & R_{24}
\end{array}$$

(In the formula, R_{21} to R_{24} each represent a substituted or unsubstituted alkyl or alkenyl group having 1 to 5 carbon atoms, or a substituted or unsubstituted phenyl group. R_{21} to R_{24} may be identical to or different from one another. o and p each represent an integer of 0 or more, and a sum of o and p represents an integer of 1 or more.).

Claim 4 (Original): The field effect transistor according to any one of claims 1 to 3, wherein the porphyrin is represented by the following general formula (3): General formula (3)

(In the formula, R_{11} 's represent at least one kind selected from the group consisting of a hydrogen atom, a halogen atom, a hydroxyl group, or an alkyl, oxyalkyl, thioalkyl, or alkylester group having 1 to 12 carbon atoms, and R_{11} 's may be identical to or different from one another. In addition, adjacent R_{11} 's may form an aromatic ring which may have a substituent. In addition, the adjacent R_{11} 's may be connected to another porphyrin ring which may have a substituent through the formed aromatic ring. R_{12} 's represent at least one kind selected from the group consisting of a hydrogen atom and an aryl group which may have a substituent. R_{12} 's may be identical to or different from one another. X represents a hydrogen atom or a metal atom.).

Claim 5 (Currently Amended): The field effect transistor according to any one of claims 1 to claim 4, wherein at least one pair of the adjacent R₁₁'s in the general formula (3) forms an aromatic ring.

Claim 6 (Currently Amended): The field effect transistor according to any one of claims 1 to 5 claim 4, wherein the aromatic ring formed by the at least one pair of the adjacent R₁₁'s in the general formula (3) is obtained by heating a precursor having a bicyclo[2.2.2]octadiene skeleton structure which may have a substituent.

Claim 7 (Currently Amended): The field effect transistor according to any one of claims 1 to 6 claim 1, wherein Bragg angles (20) of $CuK\alpha$ X-ray diffraction in the organic semiconductor layer have peaks at $8.3^{\circ} \pm 0.2^{\circ}$, $10.1^{\circ} \pm 0.2^{\circ}$, $11.8^{\circ} \pm 0.2^{\circ}$, and $14.4^{\circ} \pm 0.2^{\circ}$.

Claim 8 (Currently Amended): The field effect transistor according to any one of claims 1 to 6 claim 1, wherein Bragg angles (2 θ) of CuK α X-ray diffraction in the organic semiconductor layer have peaks at 8.4° \pm 0.2°, 11.9° \pm 0.2°, and 16.9° \pm 0.2°.

Claim 9 (Currently Amended): The field effect transistor according to any one of claims 1 to 6 claim 1, wherein Bragg angles (20) of CuK α X-ray diffraction in the organic semiconductor layer have peaks at 7.2° \pm 0.2°, 7.8° \pm 0.2°, 11.7° \pm 0.2°, and 23.5° \pm 0.2°.

Claim 10 (Currently Amended): The field effect transistor according to any one of claims 1 to 6 claim 1, wherein Bragg angles (20) of CuK α X-ray diffraction in the organic semiconductor layer have peaks at 7.3°± 0.2°, 7.8°± 0.2°, 11.7° ± 0.2°, and 19.6° ± 0.2°.

Claim 11 (Original): A method of producing a field effect transistor having an organic semiconductor layer, comprising the step of laminating an organic semiconductor layer containing at least porphyrin and a layer composed of at least a polysiloxane compound in such a manner that the layers are in intimate contact with each other.

Claim 12 (Original): The method of producing a field effect transistor according to claim 11, wherein the polysiloxane compound is represented by the following general formula (1):

General formula (1)

$$\begin{array}{c|c}
 & R_1 & R_3 \\
 & S_1 & S_1 \\
 & R_2 & R_4
\end{array}$$

(In the formula, R_1 to R_4 each represent a substituted or unsubstituted alkyl or alkenyl group having 1 to 5 carbon atoms, a substituted or unsubstituted phenyl group, or a siloxane unit. R_1 to R_4 may be identical to or different from one another. n represents an integer of 1 or more.).

Claim 13 (Original): The method of producing a field effect transistor according to claim 11, wherein the polysiloxane compound comprises a polysiloxane compound represented by the following general formula (2) and/or the following general formula (6):

General formula (2)

(In the formula, R_7 to R_{10} each represent a substituted or unsubstituted alkyl or alkenyl group

having 1 to 5 carbon atoms, or a substituted or unsubstituted phenyl group. R_7 to R_{10} may be identical to or different from one another. m and n each represent an integer of 0 or more, and a sum of m and n is an integer of 1 or more.)

General formula (6)

$$\begin{array}{c|c}
 & R_{21} \\
 & S_{i} \\$$

(In the formula, R_{21} to R_{24} each represent a substituted or unsubstituted alkyl or alkenyl group having 1 to 5 carbon atoms, or a substituted or unsubstituted phenyl group. R_{21} to

R₂₄ may be identical to or different from one another. o and p each represent an integer of 0 or more, and a sum of o and p is an integer of 1 or more.).

Claim 14 (Original): A method of producing a field effect transistor according to any one of claims 11 to 13, wherein the porphyrin is represented by the following general formula (3):

General formula (3)

$$R_{11}$$
 R_{12}
 R_{11}
 R_{12}
 R_{11}
 R_{12}
 R_{11}
 R_{12}
 R_{11}
 R_{11}
 R_{11}
 R_{12}
 R_{11}

(In the formula, R_{11} 's represent at least one kind selected from the group consisting of a hydrogen atom, a halogen atom, a hydroxyl group, or an alkyl, oxyalkyl, thioalkyl, or alkylester group having 1 to 12 carbon atoms, and R_{11} 's may be identical to or different from one another. In addition, adjacent R_{11} 's may form an aromatic ring which may have a substituent. In addition, the adjacent R11's may be connected to a porphyrin ring which may have a substituent through the formed aromatic ring. R_{12} 's represent at least one kind selected from the group consisting of a hydrogen atom and an aryl group which may have a

substituent. R_{12} 's may be identical to or different from one another. X represents a hydrogen atom or a metal atom.).

Claim 15 (Currently Amended): The method of producing a field effect transistor according to any one of claims 11 to claim 14, wherein at least one pair of the adjacent R_{11} 's in the general formula (3) forms an aromatic ring.

Claim 16 (Currently Amended): The method of producing a field effect transistor according to any one of claims 11 to 15 claim 14, wherein the aromatic ring formed by the at least one pair of the adjacent R_{11} 's in the general formula (3) is obtained by heating a precursor having a bicyclo[2.2.2]octadiene skeleton structure which may have a substituent.

Claim 17 (Currently Amended): The method of producing a field effect transistor according to any one of claims 11 to 16 claim 11, wherein Bragg angles (20) of $CuK\alpha$ X-ray diffraction in the organic semiconductor layer form peaks at $8.3^{\circ} \pm 0.2^{\circ}$, $10.1^{\circ} \pm 0.2^{\circ}$, $11.8^{\circ} \pm 0.2^{\circ}$, and $14.4^{\circ} \pm 0.2^{\circ}$.

Claim 18 (Currently Amended): The method of producing a field effect transistor according to any one of claims 11 to 16 claim 11, wherein Bragg angles (20) of $CuK\alpha$ X-ray diffraction in the organic semiconductor layer form peaks at $8.4^{\circ} \pm 0.2^{\circ}$, $11.9^{\circ} \pm 0.2^{\circ}$, and $16.9^{\circ} \pm 0.2^{\circ}$.

Claim 19 (Currently Amended): The method of producing a field effect transistor according to any one of claims 11 to 16 claim 11, wherein Bragg angles (20) of $CuK\alpha$ X-ray diffraction in the organic semiconductor layer form peaks at $7.2^{\circ} \pm 0.2^{\circ}$, $7.8^{\circ} \pm 0.2^{\circ}$, $11.7^{\circ} \pm 0.2^{\circ}$, and $23.5^{\circ} \pm 0.2^{\circ}$.

Claim 20 (Currently Amended): The method of producing a field effect transistor according to any one of claims 11 to 16 claim 11, wherein Bragg angles (20) of $CuK\alpha$ X-ray diffraction in the organic semiconductor layer form peaks at $7.3^{\circ} \pm 0.2^{\circ}$, $7.8^{\circ} \pm 0.2^{\circ}$, $11.7^{\circ} \pm 0.2^{\circ}$, and $19.6^{\circ} \pm 0.2^{\circ}$.

Claim 21 (Original): A method of producing a laminated member having an organic semiconductor layer, comprising the steps of:

providing a crystallization promoting layer on a substrate;

providing an organic semiconductor precursor on the crystallization promoting layer; and

applying energy to the organic semiconductor precursor to form a layer composed of an organic semiconductor.

Claim 22 (Original): The method of producing a laminated member according to claim 21, wherein the crystallization promoting layer has a function of promoting bonding between crystal grains.

Claim 23 (Original): The method of producing a laminated member according to claim 21 or 22, wherein the energy comprises light energy or heat energy.

Claim 24 (Currently Amended): The method of producing a laminated member according to any one of claims 21 to 23 claim 21, wherein the step of applying energy to the organic semiconductor precursor to form the layer composed of the organic semiconductor includes a step of allowing the organic semiconductor precursor to cause an elimination reaction.

Claim 25 (Original): The method of producing a laminated member according to claim 24, wherein the elimination reaction comprises a retro Diels-Alder reaction.

Claim 26 (Original): The method of producing a laminated member according to claim 24 or 25, wherein the energy is continuously applied even after completion of the elimination reaction.

Claim 27 (Currently Amended): The method of producing a laminated member according to any one of claims 21 to 26 claim 21, wherein the step of providing the organic semiconductor precursor comprises a step of applying or printing a solution containing the organic semiconductor precursor.

Claim 28 (Currently Amended): The method of producing a laminated member according to any one of claims 21 to 27 claim 21, wherein the crystallization promoting layer contains a polysiloxane compound.

Claim 29 (Original): A method of producing a field effect transistor having an organic semiconductor layer, comprising the steps of:

forming a crystallization promoting layer on a substrate;

providing an organic semiconductor precursor on the crystallization promoting layer; and

providing energy to the organic semiconductor precursor to form the organic semiconductor layer.

Claim 30 (Original): The method of producing a field effect transistor according to claim 29, wherein the crystallization promoting layer has a function of promoting bonding between crystal grains.

Claim 31 (Original): The method of producing a field effect transistor according to claim 29 or 30, wherein the energy comprises light energy or heat energy.

Claim 32 (Currently Amended): The method of producing a field effect transistor according to any one of claims 29 to 31 claim 29, wherein the step of applying energy to the organic semiconductor precursor to form a layer composed of an organic

semiconductor includes a step of allowing the organic semiconductor precursor to cause an elimination reaction.

Claim 33 (Original): The method of producing a field effect transistor according to claim 32, wherein the elimination reaction comprises a reverse Diels-Alder reaction.

Claim 34 (Original): The method of producing a field effect transistor according to claim 32 or 33, wherein the energy is continuously applied even after completion of the elimination reaction.

Claim 35 (Currently Amended): The method of producing a field effect transistor according to any one of claims 29 to 34 claim 29, wherein the step of providing the organic semiconductor precursor comprises a step of applying or printing a solution containing the organic semiconductor precursor.

Claim 36 (Currently Amended): The method of producing a field effect transistor according to any one of claims 29 to 35 claim 29, wherein the crystallization promoting layer contains a polysiloxane compound.

Claim 37 (Original): A field effect transistor having an organic semiconductor layer, comprising:

a substrate;

a crystallization promoting layer on the substrate; and the organic semiconductor layer in contact with the crystallization promoting layer.